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(54) METHOD FOR REFINING HYDROGEN PEROXIDE WATER

(57)Abstract:

PURPOSE: To obtain hydrogen peroxide water of high purity which is extremely low in the concn. of metal components which are impurities and is most adequately usable for a process for producing semiconductors by bringing ion exchange resins used for refining of the hydrogen peroxide water into contact with an aq. mineral acid soln. of high purity and ultra-pure water, thereby pretreating these resins.

CONSTITUTION: Strongly acidic cation exchange resins and/or strongly basic anion exchange resins are used as the ion exchange resins. The concn. of the metal component of the high-purity aq. mineral acid soln. is specified to ≤ 50.1 ppb and the concn. of the metal component of the ultra-pure water to ≤ 0.1 ppb. The hydrogen peroxide water industrially produced by an anthraquinone method, etc., is usable as the crude hydrogen peroxide water used for refining. A column liquid path method is preferable in terms of working efficiency for the contact treatment of the ion exchange resins. The liquid pass velocity is specified to 0.1 to 50hr⁻¹, the amt. of the high-purity mineral acid used for the pretreatment to ≥ 50 times the resin amt. and the volume of the ultra-pure water is specified to ≥ 10 times the resin amt. The contact temp. is specified to $\leq 30^\circ$ C.

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